

ABSTRACT OF THE DISCLOSURE

A method for efficiently and completely removing a film deposited inside a film forming chamber and a CVD apparatus having a hot element to which an in-situ cleaning method can be applied, and an in-situ cleaning method.

The removal method of this invention comprises a method for removing a film deposited inside a chamber which can be exhausted and/or on a member placed in the chamber, wherein after the chamber is exhausted, a hot element, at least the surface of which is composed of platinum, disposed in said vacuum chamber, is heated at a prescribed temperature and a cleaning gas which is decomposed and/or activated by the hot element to generate an activated species that converts the deposited film into gaseous substance is introduced into the chamber.

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